

**Notice of References Cited**

Application/Control No.

09/972,428

Applicant(s)/Patent Under  
Reexamination  
PIERRAT ET AL.

Examiner

John Ruggles

Art Unit

1756

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,573,890	11-1996	Spence, Christopher A.	430/311
	B	US-6,040,892	03-2000	Pierrat, Christophe	355/53
*	C	US-5,424,154	06-1995	Borodovsky, Yan A.	430/5
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Hideyuki Jinbo and Yoshio Yamashita, "0.2 um or Less i-Line Lithography by Phase-Shifting-Mask Technology", 1990, IEEE, pages 33.3.1-33.3.4
*	V	Alexander S. Wong, David M. Newmark, J. Brett Rolfson, Randy J. Whiting, and Andrew R. Neureuther, "Investigating Phase-Shifting Mask Layout Issues Using a CAD Toolkit", 1991, IEEE, pages 27.4.1-27.4.4
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.